

EAST Search History

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L1	4376	((phas\$3 or shift\$3) near2 (mask or photomask or reticle) or PSM).ti,ab.	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2006/09/11 18:42
L2	786	1 and ((attenuat\$3 or halftone or half tone) with (phas\$3 or shift\$3 or PS or PSM) or attPSM or att PSM or HPSM or H PSM).ti,ab.	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2006/09/11 18:44
L3	214	2 and ((etch\$3 or groov\$3 or recess\$3 or mesa or rais\$3 or thick\$4) with (phas\$3 or shift\$3 or PS or PSM) or attPSM or att PSM or HPSM or H PSM).ti,ab.	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2006/09/11 18:45
L4	94	3 and ((blank or wavelength or wave length) with (phas\$3 or shift\$3 or mask or photomask or reticle or PS or PSM) or attPSM or att PSM or HPSM or H PSM).ti,ab.	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2006/09/11 18:46
L5	8318	430/5.ccls.	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2006/09/11 18:46
L6	419	216/12.ccls.	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2006/09/11 18:49
L7	53	3 and (5 or 6) not 4	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2006/09/11 19:05
L8	232	2 and (5 or 6) not 4 not 7	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2006/09/11 18:51
L9	11	8 and (reactive ion near2 etch\$3 or RIE) with ("SF.sub.6" or "CF.sub.4" or sulfur hexafluoride or carbon tetrafluoride)	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2006/09/11 18:53
L10	1	2 and (reactive ion near2 etch\$3 or RIE) with ("SF.sub.6" or "CF.sub.4" or sulfur hexafluoride or carbon tetrafluoride) not 4 not 7 not 9	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2006/09/11 18:53
L11	2	3 and ((blank or wavelength or wave length) with (phas\$3 or shift\$3 or mask or photomask or reticle or PS or PSM) or attPSM or att PSM or HPSM or H PSM) not 4 not 7 not 9 not 10	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2006/09/11 18:56

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L12	1	3 and ((second or third or plural or multiple) with (wavelength or wave length or thick\$4) same (phas\$3 or shift\$3 or mask or photomask or reticle or PS or PSM) or attPSM or att PSM or HPSM or H PSM).ti,ab. not 4 not 7 not 9 not 10 not 11	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2006/09/11 18:57
L13	4	3 and ((second or third or plural or multiple) same (wavelength or wave length or thick\$4) same (phas\$3 or shift\$3 or PSM) or attPSM or att PSM or HPSM or H PSM).ti,ab. not 4 not 7 not 9 not 10 not 11 not 12	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2006/09/11 19:00
L14	5	2 and ((second or third or plural or multiple) same (wavelength or wave length or thick\$4) same (phas\$3 or shift\$3 or PSM) or attPSM or att PSM or HPSM or H PSM).ti,ab. not 4 not 7 not 9 not 10 not 11 not 12 not 13	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2006/09/11 19:02
L15	123	2 and ((second or third or plural or multiple) same (wavelength or wave length or thick\$4) same (phas\$3 or shift\$3 or PSM) or attPSM or att PSM or HPSM or H PSM) not 4 not 7 not 9 not 10 not 11 not 12 not 13 not 14	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2006/09/11 19:04
L16	70	15 and ((transmi\$6 or transpar\$6) same ((attenuat\$3 or halftone or half tone) same (phas\$3 or shift\$3 or PSM)) or attPSM or att PSM or HPSM or H PSM).ti,ab.	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2006/09/11 19:03
L17	7	((Cheng Ming or ChengMing) near2 Lin).in. not 4 not 7 not 9 not 10 not 11 not 12 not 13 not 14 not 16	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2006/09/11 19:04
L18	544	(5 or 6) and (attenuat\$3 or halftone or half tone or semitranspar\$6 or semitransmi\$6 or semi (transpar\$6 or transmi\$6) or partial\$2 (transpar\$6 or transmi\$6) or attPSM or att PSM or HPSM or H PSM).ti,ab.	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2006/09/11 19:06
L19	21	18 and ((wavelength or wave length) and (thick\$4 or depth)).ti, ab.	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2006/09/11 19:07
L20	55	18 and (wavelength or wave length).ti,ab. not 19	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2006/09/11 19:10

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L21	138	18 and (transmit\$5 or transmis\$6 or transparen\$3) same (equation or expression or formula)	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2006/09/11 19:11
L22	148	18 and (phas\$3 or shift\$3 or PS) same (equation or expression or formula)	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2006/09/11 19:11
L23	108	21 and 22	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2006/09/11 19:11
L24	17	(mask or photomask or reticle or PSM) near3 blank same (different or other or another or plural or multiple) near3 (company or organization or corporation or enterprise or establishment or firm or outfit or crafter or business or fabricator or creator or builder or producer or assembler or manufacturer or maker or supplier)	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2006/09/11 19:12
L25	0	((phas\$3 or shift\$3) near2 (mask or photomask or reticle) or PSM) and (attenuat\$3 or halftone or half tone or attPSM or att PSM or HPSM or H PSM) and (wavelength or wave length) and blank and etch\$3 and (transmit\$5 or transmis\$6 or transparen\$3) and (light\$3 or radiat\$3) and thickness and (company or organization or corporation or enterprise or establishment or firm or outfit or crafter or business or fabricator or creator or builder or producer or assembler or manufacturer or maker or supplier)).clm.	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2006/09/11 19:31
L26	8	((phas\$3 or shift\$3) near2 (mask or photomask or reticle) or PSM) and (attenuat\$3 or halftone or half tone or attPSM or att PSM or HPSM or H PSM) and (wavelength or wave length) and blank and etch\$3 and (transmit\$5 or transmis\$6 or transparen\$3) and (light\$3 or radiat\$3) and thickness).clm.	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2006/09/11 19:31